

**IN THE SPECIFICATION**

Please replace the following numbered paragraphs with the following rewritten paragraphs:

[0031] In step 340, ~~In addition~~, the first matching network can be tuned to an initial value, the first RF source can provide a first top RF (TRF) signal to the first electrode in the processing chamber. The first TRF signal can be characterized by a first TRF frequency (TRF1) and a first TRF power level.

[0033] ~~In~~ Further in step 340, after a plasma is ignited, the first RF source provides a second TRF signal to the first electrode in the processing chamber. The second TRF signal can be characterized by a second TRF frequency (TRF2) and a second TRF power level.

[0034] For example, in step 340, the first RF source can perform a frequency step from TRF1 to TRF2. In one embodiment of the present invention, the frequency step can be at least ten percent of the first frequency. In other words, TRF2 can be greater than  $1.1 \times (\text{TRF1})$  or less than  $0.9 \times (\text{TRF1})$ . In another embodiment, the frequency step can be at least two percent of the first frequency. In other words, TRF2 can be greater than  $1.02 \times (\text{TRF1})$  or less than  $0.98 \times (\text{TRF1})$ .

[0035] Preferably, in step 350, the second TRF power level can be greater than fifty percent of the first TRF power level. Lower power output requirement for the second TRF power level permits the RF frequency source to be less expensive.

[0041] ~~In step 350, the~~ In general, the plasma is sustained by providing a third RF signal to the processing chamber. The third RF signal can be at the first frequency and a third power. For example, the third power can be approximately equal to the first power. Alternately, the third RF signal can be at a different frequency and/or a different power.